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ROMIL
PURE CHEMISTRY

RIKI GLOBAL

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ROMIL-PUROM™ High Purity Process Solvents Specifications

for industrial applications

Acetic Acid glacial (see Acetic Acid)

Acetic Acid PUROM *P5014*

25LT P5014G
200LT P5014D
Dgr H:226-314
P:280c-301+330+331-305+351+338-307+310

(Acetic Acid glacial)
CH3COOH MW 60.05 FP 16.7°C BP 117.9°C d 1.05 CAS [64-19-7] Assay >99.8% Water <0.1% Residue <0.0005%
Application: High purity process solvent

Acetone PUROM *P5031*

25LT P5031G
200LT P5031D
Dgr H:225-319-336-EUH066
P:210-233-305+351+338

(Propanone)
(CH3)2COMW 58.08 BP 56.1°C d 0.79 CAS [67-64-1]
Assay >99.9% Water <0.2% Residue <0.0005%
Application: High purity process solvent

Acetonitrile PUROM *P5048*

25LT P5048G
200LT P5048D
Dgr H:225-302+312+332-319
P:210-240-302+352-305+351+338-403+233

(Methyl Cyanide)
CH3CNMW 41.05 BP 81.6°C d 0.78 CAS [75-05-8]
Assay >99.9% Water <0.01% Residue <0.0005%
Application: High purity process solvent

Acetonitrile PUROM
for preparative HPLC *P5046*

25LT P5046G
200LT P5046D
Dgr H:225-302+312+332-319
P:210-240-302+352-305+351+338-403+233

(Methyl Cyanide)
CH3CNMW 41.05 BP 81.6°C d 0.78 CAS [75-05-8]
Assay >99.9% Water <0.03% Residue <0.0005%
UV: 230nm >70%; 280nm >95%
Application: High purity process solvent for preparative HPLC

n-Butanol (see Butan-1-ol)

n-Butyl Alcohol (see Butan-1-ol)

tert-Butyl Methyl Ether (see Methyl tert-Butyl Ether)

Butan-1-ol PUROM *P5083*

25LT P5083G
200LT P5083D
Dgr H:226-302-315-318-335-336
P:210-280f-302+352-304+340-305+351+338-313

(n-Butanol, n-Butyl Alcohol)
CH3(CH2)3OH MW74.12 BP 117.7°C d 0.81 CAS [71-36-3]
Assay >99.8% Water <0.05% Residue <0.0005%
Application: High purity process solvent

Chloroform PUROM
stabilised with amylene *P5140*

200LT P5140D
Dgr H:351-361d-331-302-372-319-315
P:261v-280f-304+340-305+351+338-308+313

(Trichloromethane)
CHCl3 MW119.38 BP 61.2°C d 1.48 CAS [67-66-3]
Assay >99.9%* Water <0.005% Residue <0.0005%
*ex stabiliser
Stabiliser: Amylene ca. 25 ppm
Application: High purity process solvent

Chloroform PUROM
stabilised with ethanol *P5135*

200LT P5135D
Dgr H:351-361d-331-302-372-319-315
P:261v-280f-304+340-305+351+338-308+313

(Trichloromethane)
CHCl3 MW119.38 BP 61.2°C d 1.48 CAS [67-66-3]
Assay >99.9%* Water <0.005% Residue <0.0005%
*ex stabiliser
Stabiliser: Ethanol ca. 1% w/w
Stabiliser should only be removed immediately before use by adsorption onto activated alumina.
Application: High purity process solvent

ROMIL-PUROM™ High Purity Process Solvents Specifications

for industrial applications

Dichloromethane PUROM

stabilised with amylene *P5202*

25LT P5202G
200LT P5202D
Wng H:351
P:281-308+313

(Methylene Dichloride)
CH2Cl2MW84.93BP 39.6°C d 1.33 CAS [75-09-2]
Assay >99.9%* Water <0.01% Residue <0.0005%
*ex stabiliser
Stabiliser: Amylene ca. 25 ppm
Application:Highpurity processsolvent

Diethyl Ether PUROM

stabilised with BHT *P5220*

25LT P5220G
200LT P5220D
Dgr H:224-302-336-EUH019-EUH066
P:210-240-403+235

(C2H5)2O MW 74.12 BP 34.4°C d 0.71 CAS [60-29-7]
Assay >99.9%* Water <0.02% Residue <0.0005%*
*ex stabiliser
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Stabiliser: Butylated hydroxytoluene (BHT) ca. 5 ppm
Application: High purityprocesssolvent

1,2-Dimethoxyethane PUROM *P5261*

25LT P5261G
200LT P5261D
Dgr H:225-360FD-332-EUH019 P:201-210-308+313-403+235

(Ethylene Glycol Dimethyl Ether)
CH3OCH2CH2OCH3 MW90.12 FP -58°C BP 85°C d 0.87 CAS [110-71-4] Assay >99.9% Water <0.01% Residue <0.0005%
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

Dimethylformamide PUROM *P5253*

25LT P5253G
200LT P5253D
Dgr H:360D-226-312+332-319
P:201-210-302+352-305+351+338-308+313

HCON(CH3)2 MW 73.09 BP 153.0°C d 0.95CAS[68-12-2]
Assay >99.9% Water <0.03% Residue <0.0005%
Application: High purity process solvent

1,4-Dioxan PUROM *P5297*

25LT P5297G
200LT P5297D
Dgr H:225-350-319-335-EUH019-EUH066
P:210-281-305+351+338-308+313

C4H8O2MW 88.11 FP 11.8°C BP101.3°C d 1.03 CAS [123-91-1]
Assay >99.9% Water <0.005% Residue <0.0005%
Unstabilised
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

Ethyl Alcohol (see Ethanol)

Ethylene Glycol Dimethyl Ether (see 1,2-Dimethoxyethane)

Ethanol absolute PUROM *P5314*

25LT P5314G
200LT P5314D
Dgr H:225
P:210-233-240-403+235

(Ethyl Alcohol)
C2H5OHMW 46.07 BP 78.3°C d 0.79 CAS [64-17-5]
Assay >99.8% Water <0.1% Residue <0.0005%
Application: High purity process solvent

Ethyl Acetate PUROM *P5346*

25LT P5346G
200LT P5346D
Dgr H:225-319-336-EUH066
P:210-233-240-305+351+338-403+235

CH3COOC2H5 MW 88.11 BP 77.1°Cd 0.90 CAS [141-78-6]
Assay >99.9% Water <0.005% Residue <0.0005%
Application: High purity process solvent

n-Heptane 95% PUROM *P5367*

25LT P5367G
200LT P5367D
Dgr H:225-304-315-336-410
P:210-273-301+310-331-302+352-304+340-403+235

CH3(CH2)5CH3 MW 100.21BP94-98°Cd 0.68 CAS [142-82-5]
Water <0.005% Residue <0.0005%
Assay (n-isomer) >95%
Assay (all isomers) >99.5%
Application: High purity process solvent

ROMIL-PUROM™ High Purity Process Solvents Specifications

for industrial applications

n-Heptane 99% PUROM *P5366*

25LT P5366G
200LT P5366D
Dgr H:225-304-315-336-410
P:210-273-301+310-331-302+352-304+340-403+235

CH3(CH2)5CH3MW 100.21 BP98.4°C d0.68 CAS [142-82-5]
Assay >99% Water <0.005% Residue <0.0005%
Application: High purity process solvent

Hexane fraction PUROM *P5390*

25LT P5390G
200LT P5390D
Dgr H:225-304-361f-373-315-336-411
P:210-240-273-301+310-331-302+352-403+235

C6H14 BP 65-70°C d 0.66 CAS [73513-42-5]
Water <0.005% Residue <0.0005%
Comprises ca. 50% n-isomer, the remainder being predominantly other isomers of hexane.
Application: High purity process solvent

iso-Hexane 95% PUROM *P5388*

25LT P5388G
200LT P5388D
Dgr H:225-304-315-336-411
P:233-273-301+310-331-302+352-403+235

C6H14 MW86.18BP55-63°Cd0.65CAS[107-83-5]
Water <0.005% Residue <0.0005%
n-Hexane <5%
Application: High purity process solvent

n-Hexane 95% PUROM *P5389*

25LT P5389G
200LT P5389D
Dgr H:225-304-361f-373-315-336-411
P:210-240-273-301+310-331-302+352-403+235

CH3(CH2)4CH3 MW 86.18BP67-70°Cd 0.66 CAS [110-54-3]
Water <0.005% Residue <0.0005%
Assay (n-isomer) >95%
Assay (all isomers) >99.5%
Application:High purityprocesssolvent

Methyl Alcohol (see Methanol)

Methyl Cyanide (see Acetonitrile)

Methylene Dichloride (see Dichloromethane)

4-Methylpentan-2-one (see Methyl iso-Butyl Ketone)

Methanol PUROM *P5410*

25LT P5410G
200LT P5410D
Dgr H:225-301+311+331-370
P:210-280f-302+352-309+310-403+235

(Methyl Alcohol)
CH3OHMW 32.04 BP 64.5°C d 0.79 CAS [67-56-1]
Assay >99.9% Water <0.02% Residue <0.0005%
Application: High purity process solvent

Methanol PUROM
for preparative HPLC *P5408*

25LT P5408G
200LT P5408D
Dgr H:225-301+311+331-370
P:210-280f-302+352-309+310-403+235

(Methyl Alcohol)
CH3OHMW 32.04 BP 64.5°C d 0.79 CAS [67-56-1]
Assay >99.8% Water <0.05% Residue <0.0005%
UV: 225nm >50%; 255nm >95%
Application: High purity process solvent for preparative HPLC

Methyl tert-Butyl Ether PUROM *P5447*

25LT P5447G
200LT P5447D
Dgr H:225-315
P:210-233-302+352-403+235

(tert-Butyl Methyl Ether)
CH3OC(CH3)3 MW 88.15 BP 55.4°C d 0.74 CAS [1634-04-4] Assay >99.7% Water <0.02% Residue <0.0005%
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

2-Methyltetrahydrofuran PUROM *P5536*

25LT P5536G
200LT P5536D
Dgr H:225-319-335-EUH019
P:210-233-240-305+351+338-403+235

CH3C4H7OMW86.13 BP80°Cd0.86 CAS[96-47-9] Assay >99.8% Water <0.01% Residue <0.0005% Unstabilised
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

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ROMIL-PUROM™ High Purity Process Solvents Specifications

for industrial applications

2-Methyltetrahydrofuran PUROM

stabilised with BHT *P5537*

25LT P5537G
200LT P5537D
Dgr H:225-319-335-EUH019
P:210-233-240-305+351+338-403+235

CH3C4H7O MW 86.13 BP 80°C d 0.86 CAS [96-47-9]
Assay >99.8%* Water <0.01% Residue <0.0005%*
*ex stabiliser
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Stabiliser: Butylated hydroxytoluene (BHT) ca. 250 ppm
Application: High purity process solvent

iso-Octane (see 2,2,4-Trimethylpentane)

Perchloroethylene (see Tetrachloroethylene)

Petroleum Distillate (see Petroleum Ether)

Petroleum Spirit (see Petroleum Ether)

n-Propanol (see Propan-1-ol)

iso-Propanol (see Propan-2-ol)

Propanone (see Acetone)

n-Propyl Alcohol (see Propan-1-ol)

iso-Propyl Alcohol (see Propan-2-ol)

n-Pentane 95% PUROM

P5571

25LT P5571G
200LT P5571D
Dgr H:225-304-336-411-EUH066
P:273-301+310-331-403+235

CH3(CH2)3CH3 MW 72.15BP35.5-37°Cd 0.63 CAS [109-66-0]
Water <0.005% Residue <0.0005%
Assay (n-isomer) >95%
Assay (all isomers) >99.5%
Application: High purity process solvent

Petroleum Ether 40-60°C PUROM

P5601

25LT P5601G
200LT P5601D
Dgr H:225-304-336-411-EUH066
P:210-233-243-273-280-301+310-303+361+353-304+340-331-403+235

(Petroleum Distillate, Petroleum Spirit)
BP40-60°C d 0.64 CAS [8032-32-4]
Water <0.005% Residue <0.0005%
Application: High purity process solvent

Petroleum Ether 60-80°C PUROM

P5602

25LT P5602G
200LT P5602D
Dgr H:225-304-315-336-411
P:210-243-273-280-301+310-331-403+235

(Petroleum Distillate, Petroleum Spirit)
BP60-80°C d 0.67
Water <0.005% Residue <0.0005%
Application: High purity process solvent

Propan-1-ol PUROM

P5624

25LT P5624G
200LT P5624D
Dgr H:225-318-336
P:210-233-280f-305+351+338-313

(n-Propanol, n-Propyl Alcohol)
CH3CH2CH2OH MW 60.10 BP 97.2°C d 0.80 CAS [71-23-8] Assay >99.9% Water <0.05% Residue <0.0005%
Application: High purity process solvent

Propan-2-ol PUROM

P5625

25LT P5625G
200LT P5625D
Dgr H:225-319-336
P:210-233-305+351+338

(iso-Propanol, iso-Propyl Alcohol)
(CH3)2CHOH MW 60.10 BP 82.2°C d 0.78 CAS [67-63-0]
Assay >99.9% Water <0.02% Residue <0.0005%
Application: High purity process solvent

ROMIL-PUROM™ High Purity Process Solvents Specifications

for industrial applications

Trichloromethane (see Chloroform)

Tetrachloroethylene PUROM — P5702

25LT P5702G
200LT P5702D
Wng H:315-317-319-336-351-411
P:273-281-302+352-305+351+338-308+313

(Perchloroethylene)
CCl2CCl2MW 165.83 BP 121.1°C d 1.62 CAS [127-18-4]
Assay >99.9% Water <0.005% Residue <0.0005%
Unstabilised
Application: High purity process solvent

Tetrahydrofuran PUROM — P5718

25LT P5718G
200LT P5718D
Dgr H:225-319-335-351-EUH019
P:210-240-305+351+338-308+313-403+233

CH2(CH2)2CH2OMW 72.11BP 66.0°C d0.89 CAS [109-99-9]
Assay >99.9% Water <0.005% Residue <0.0005%
Unstabilised
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

Tetrahydrofuran PUROM
stabilised with BHT — P5719

25LT P5719G
200LT P5719D
Dgr H:225-319-335-351-EUH019
P:210-240-305+351+338-308+313-403+233

CH2(CH2)2CH2O MW 72.11 BP 66.0°C d 0.89 CAS [109-99-9] Assay >99.9%* Water <0.005% Residue <0.0005%*
*ex stabiliser
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Stabiliser: Butylated hydroxytoluene (BHT) ca. 250 ppm
Application: High purity process solvent

Toluene PUROM — P5771

25LT P5771G
200LT P5771D
Dgr H:225-304-315-336-361d-373
P:210-240-301+310-331-302+352-403+235

C6H5CH3MW 92.14 BP 110.6°C d 0.87 CAS [108-88-3]
Assay >99.9% Water <0.01% Residue <0.0005%
Application: High purity process solvent

2,2,4-Trimethylpentane PUROM — P5901

25LT P5901G
200LT P5901D
Dgr H:225-304-315-336-410
P:210-233-240-273-301+310-331-302+352-304+340-403+235

(iso-Octane)
(CH3)3CCH2CH(CH3)2 MW 114.23 BP 99.2°C d 0.69 CAS [540-84-1]
Assay>99.75%Water <0.005% Residue<0.0005%
Application:Highpurityprocess solvent

Water PUROM — P5950

25LT P5950G
200LT P5950D

H2OMW 18.02 FP 0.0°CBP 100.0°C CAS [7732-18-5]
Residue <0.0001%
Resistivity (at time of manufacture) >18 MOhm @ 25°C
pH (at time of manufacture) 5.5-8.0 @ 25°C
Application: High purityprocess solvent

Water PUROM
for preparative HPLC — P5948

25LT P5948G
200LT P5948D

H2O MW 18.02 FP 0.0°C BP 100.0°C d 1.00 CAS [7732-18-5]
Residue <0.0005%
Resistivity (at time of manufacture) >18 MOhm @ 25°C
pH (at time of manufacture) 5.5-8.0 @ 25°C
TOC (at time of manufacture) <50 ppb
Application: High purity process solvent for preparative HPLC

Xylene mixed isomers PUROM — P5982

25LT P5982G
200LT P5982D
Wng H:226-312+332-315 P:210-302+352-304+340

C6H4(CH3)2 MW106.17BP138-142°Cd0.86CAS[1330-20-7]
Water <0.01% Residue <0.0005%
Comprises 3 isomers and ethylbenzene
Assay (total C8H10 isomers) >98.5%
Ethylbenzene typically <3%
Toluene typically <0.5%
Methylethylbenzene typically <0.5%
Application: High purity process solvent

ROMIL-PUROM™ High Purity Process Solvents Specifications

for industrial applications

Trichloromethane (see Chloroform)

Tetrachloroethylene PUROM — P5702

25LT P5702G
200LT P5702D
Wng H:315-317-319-336-351-411
P:273-281-302+352-305+351+338-308+313

(Perchloroethylene)
CCl2CCl2MW 165.83 BP 121.1°C d 1.62 CAS [127-18-4]
Assay >99.9% Water <0.005% Residue <0.0005%
Unstabilised
Application: High purity process solvent

Tetrahydrofuran PUROM — P5718

25LT P5718G
200LT P5718D
Dgr H:225-319-335-351-EUH019
P:210-240-305+351+338-308+313-403+233

CH2(CH2)2CH2OMW 72.11BP 66.0°C d0.89 CAS [109-99-9]
Assay >99.9% Water <0.005% Residue <0.0005%
Unstabilised
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Application: High purity process solvent

Tetrahydrofuran PUROM
stabilised with BHT — P5719

25LT P5719G
200LT P5719D
Dgr H:225-319-335-351-EUH019
P:210-240-305+351+338-308+313-403+233

CH2(CH2)2CH2O MW 72.11 BP 66.0°C d 0.89 CAS [109-99-9] Assay >99.9%* Water <0.005% Residue <0.0005%*
*ex stabiliser
Peroxides (at time of manufacture) <0.0001% (<1 ppm)
Stabiliser: Butylated hydroxytoluene (BHT) ca. 250 ppm
Application: High purity process solvent

Toluene PUROM — P5771

25LT P5771G
200LT P5771D
Dgr H:225-304-315-336-361d-373
P:210-240-301+310-331-302+352-403+235

C6H5CH3MW 92.14 BP 110.6°C d 0.87 CAS [108-88-3]
Assay >99.9% Water <0.01% Residue <0.0005%
Application: High purity process solvent

2,2,4-Trimethylpentane PUROM — P5901

25LT P5901G
200LT P5901D
Dgr H:225-304-315-336-410
P:210-233-240-273-301+310-331-302+352-304+340-403+235

(iso-Octane)
(CH3)3CCH2CH(CH3)2 MW 114.23 BP 99.2°C d 0.69 CAS [540-84-1]
Assay>99.75%Water <0.005% Residue<0.0005%
Application:Highpurityprocess solvent

Water PUROM — P5950

25LT P5950G
200LT P5950D

H2OMW 18.02 FP 0.0°CBP 100.0°C CAS [7732-18-5]
Residue <0.0001%
Resistivity (at time of manufacture) >18 MOhm @ 25°C
pH (at time of manufacture) 5.5-8.0 @ 25°C
Application: High purityprocess solvent

Water PUROM
for preparative HPLC — P5948

25LT P5948G
200LT P5948D

H2O MW 18.02 FP 0.0°C BP 100.0°C d 1.00 CAS [7732-18-5]
Residue <0.0005%
Resistivity (at time of manufacture) >18 MOhm @ 25°C
pH (at time of manufacture) 5.5-8.0 @ 25°C
TOC (at time of manufacture) <50 ppb
Application: High purity process solvent for preparative HPLC

Xylene mixed isomers PUROM — P5982

25LT P5982G
200LT P5982D
Wng H:226-312+332-315 P:210-302+352-304+340

C6H4(CH3)2 MW106.17BP138-142°Cd0.86CAS[1330-20-7]
Water <0.01% Residue <0.0005%
Comprises 3 isomers and ethylbenzene
Assay (total C8H10 isomers) >98.5%
Ethylbenzene typically <3%
Toluene typically <0.5%
Methylethylbenzene typically <0.5%
Application: High purity process solvent